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PATTERN AND METHOD FOR MANUFACTURING DEVICE

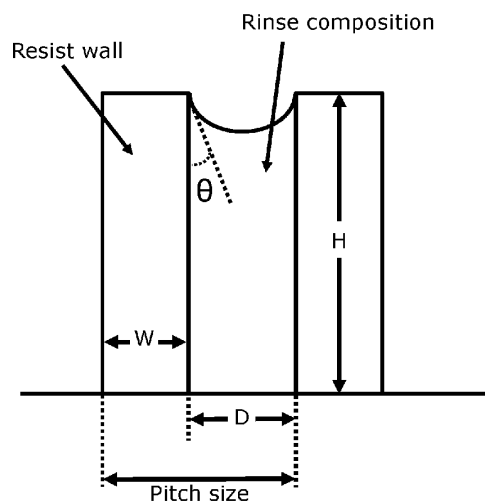


Figure 1

(57) Abstract: [Problem] To provide an electronic device manufac-
turing aqueous solution, which makes it possible to prevent pattern
collapse or suppress non-uniformity of resist pattern width. [Means
for Solution] An electronic device manufacturing aqueous solution
comprising an alkylcarboxylic acid compound (A) and a solvent (B),
wherein the alkylcarboxylic acid compound (A) is represented by the
formula (a): $A_1\text{-COOH}$ (a), wherein A_1 is C_{3-12} alkyl, and the solvent
(B) comprises water.

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